



INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification ⁶ : C08F 32/08, 232/08, C08G 61/08, G03F 7/039, 7/004	A1	(11) International Publication Number: WO 99/42502 (43) International Publication Date: 26 August 1999 (26.08.99)
(21) International Application Number: PCT/US99/03632 (22) International Filing Date: 19 February 1999 (19.02.99) (30) Priority Data: 60/075,557 23 February 1998 (23.02.98) US (71) Applicant: THE B.F. GOODRICH COMPANY [US/US]; 4020 Kinross Lakes Parkway, Richfield, OH 44286-9368 (US). (72) Inventors: JAYARAMAN, Saikumar; Apartment 211M, 9931 Darrow Park Drive, Twinsburg, OH 44087 (US). GOODALL, Brian, L.; 3959 Clover Hill Road, Akron, OH 44333 (US). RHODES, Larry, F.; 3036 Vincent Road, Silverlake, OH 44224 (US). SHICK, Robert, A.; 10375 Pamela Drive, Strongsville, OH 44136 (US). VICARI, Richard; 9937 Huntington Park Drive, Strongsville, OH 44136 (US). ALLEN, Robert, D.; 6186 Dalle del Conejo, San Jose, CA 95120 (US). OPITZ, Juliann; Apartment 3, 1670 De Marietta Avenue, San Jose, CA 95126 (US). SOORIYAKUMARAN, Ratnam; 711 Briar Ranch Lane, San Jose, CA 95120 (US). WALLOW, Thomas; 2656 Royal Ann Drive, Union City, CA 94587 (US). (74) Agent: DUNLAP, Thoburn, T.; The B.F. Goodrich Company, 9921 Brecksville Road, Brecksville, OH 44141-3289 (US).		(81) Designated States: AL, AM, AU, AZ, BA, BB, BG, BR, BY, CA, CN, CZ, EE, GE, HU, ID, IL, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, RO, RU, SD, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the</i> <i>claims and to be republished in the event of the receipt of</i> <i>amendments.</i>
(54) Title: POLYCYCLIC RESIST COMPOSITIONS WITH INCREASED ETCH RESISTANCE (57) Abstract Polycyclic polymers containing pendant aromatic moieties are disclosed. The polymers exhibit light transparency properties to deep UV wave lengths making them useful for high resolution photolithographic applications. These polymers are particularly useful in chemically amplified positive and negative tone resists.		